			DB	Time stamp
L Number	Hits	Search Text	USPAT;	2002/11/12 13:12
7	729	tungsten with silane	US-PGPUB	2002, 22, 22
			USPAT;	2002/11/12 13:12
8	46	tungsten with silane with dop\$3	US-PGPUB	2002/11/12 10:12
ļ <u></u>		1.1.1.02		2002/11/12 13:12
9	1368	tungsten with silicon with dop\$3	USPAT;	2002/11/12 13:12
			US-PGPUB	0000/11/10 13:13
10	1284	tungsten with silicon with doped	USPAT;	2002/11/12 13:13
			US-PGPUB	
11	4	tungsten with silicon with doped with	USPAT;	2002/11/12 13:13
		strength	US-PGPUB	
12	2561	(427/250-253).CCLS.	USPAT;	2002/11/12 17:51
12	2001	(121,121	US-PGPUB	
13	11	fuller.xa. with eric	USPAT;	2002/11/12 15:09
15			US-PGPUB	
14	13	((427/250-253).CCLS.) and hydroxide with	USPAT;	2002/11/12 15:11
14	13	substrate	US-PGPUB	1
1.5	37	((427/250-253).CCLS.) and hydroxide with	USPAT;	2002/11/12 15:12
15	31	((42//250-255):CCD5:) and hydroxide with	US-PGPUB	
		(substrate or surface)	USPAT;	2002/11/12 15:23
16	8	(((427/250-253).CCLS.) and hydroxide with	US-PGPUB	2002/11/12 10:20
		(substrate or surface)) and (silane or	US-PGPUB	
		Si?sub.4)		0000 /11 /10 15 23
17	195	silane with hydroxide with surface	USPAT;	2002/11/12 15:23
		· ·	US-PGPUB	1 2000 (11 (10 15 20
18	28	(silane with hydroxide with surface) and	USPAT;	2002/11/12 15:28
		(metal tungsten) with film	US-PGPUB	
19	159	semiconductor with substrate with	USPAT;	2002/11/12 15:28
		hydroxide	US-PGPUB	
20	14	(semiconductor with substrate with	USPAT;	2002/11/12 15:31
20		hydroxide) and silane	US-PGPUB	
21	742		USPAT;	2002/11/12 15:32
41	/42	with (substrate surface)	US-PGPUB	
22	11	metal with (film coating) with hydroxide	USPAT;	2002/11/12 15:32
22	11	with (substrate surface) with silane	US-PGPUB	
25	1.7		USPAT;	2002/11/12 17:32
35	17		US-PGPUB	2002, 22, 22
		hydroxide	USPAT;	2002/11/12 17:48
36	37		US-PGPUB	2002/11/12 1/110
	_	surface) with hydroxide	{	2002/11/12 17:49
37	0		USPAT;	2002/11/12 17.43
!		substrate)	US-PGPUB	2002/11/12 17:50
38	9	hydroxilated	USPAT;	2002/11/12 17:30
			US-PGPUB	0000/11/10 17 51
39	775	silane with hydroxide	USPAT;	2002/11/12 17:51
			US-PGPUB	
40	1	((427/250-253).CCLS.) and (silane with	USPAT;	2002/11/12 17:51
		hydroxide)	US-PGPUB	1
1 -	4406		USPAT;	2002/11/05 16:38
			US-PGPUB	1
_	1588	(427/255.23-255.26,255.28,255.39-255.392,25	5 USPACCLS.	2002/11/05 16:43
	1 2000	, , , , , , , , , , , , , , , , , , , ,	US-PGPUB	1
1_	8	((427/250-253).CCLS.) and (ald or atomic	USPAT;	2002/11/05 17:45
		adj layer adj deposition)	US-PGPUB	·
1_	1		USPAT;	2002/11/05 17:11
_		( 3510303 / . 21	US-PGPUB	
	35	((427/250-253).CCLS.) and sequen\$6 with	USPAT;	2002/11/05 17:25
-	35	((42//250-253).CCLS.) and sequence with (CVD or chemical adj vapor adj deposition)	US-PGPUB	
			USPAT;	2002/11/05 17:25
-	55	((4Z//ZOU-ZOS).CCLS.) and atterned with	US-PGPUB	2002, 22, 00 1, 20
		(CVD or chemical adj vapor adj deposition)	1	2002/11/05 17:44
-	7		USPAT;	2002/11/03 17:44
		or ("4851095") or ("4935661") or	US-PGPUB	
		("5356673") or ("5916365")).PN.		0000 /11 /07 17 11
-	1	("6200893").PN.	USPAT;	2002/11/05 17:44
1			US-PGPUB	
-	946	ald or atomic adj layer adj deposition	USPAT;	2002/11/05 17:45
			US-PGPUB	
1_	567	(ald or atomic adj layer adj deposition)	USPAT;	2002/11/05 17:45
	1.	and metal	US-PGPUB	
1_	94	1	USPAT;	2002/11/05 17:45
1	54	with metal	US-PGPUB	
	13		USPAT;	2002/11/05 17:46
-	13	with metal) and @ad<=19990315	US-PGPUB	
L	1	MICH HECAI) and Gad-19990313	100 10100	

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